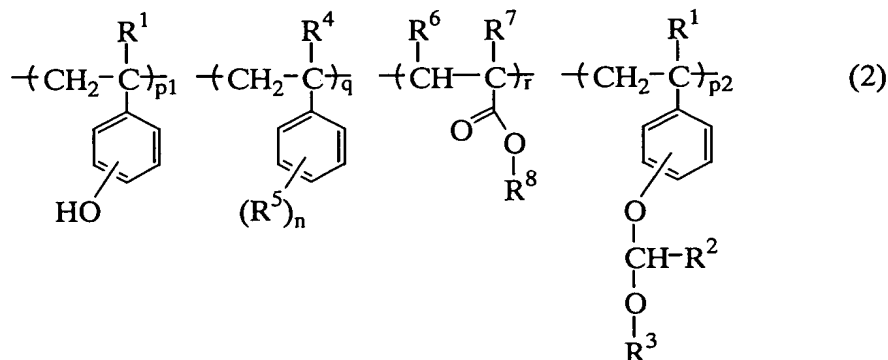
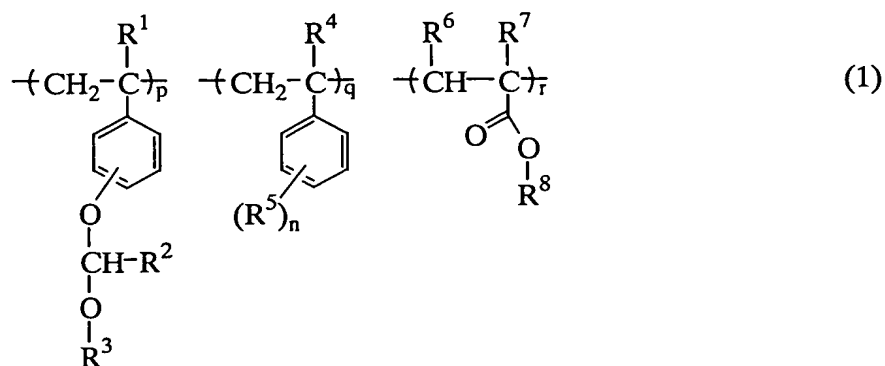


CLAIMS:

1. A method for preparing a polymer comprising recurring units of the following general formula (2), said method comprising the step of effecting deblocking reaction on a polymer comprising recurring units of the following general formula (1) in the presence of an acid catalyst,



wherein R<sup>1</sup> and R<sup>4</sup> each are hydrogen or methyl,

- 10 R<sup>2</sup> and R<sup>3</sup> each are a straight or branched alkyl group of 1 to 10 carbon atoms, or R<sup>2</sup> and R<sup>3</sup>, taken together, may form a ring,

- 15 R<sup>5</sup> is hydrogen, a hydroxyl group, straight or branched alkyl group having 1 to 10 carbon atoms, substitutable alkoxy group having 1 to 10 carbon atoms, halogen atom or acid labile group,

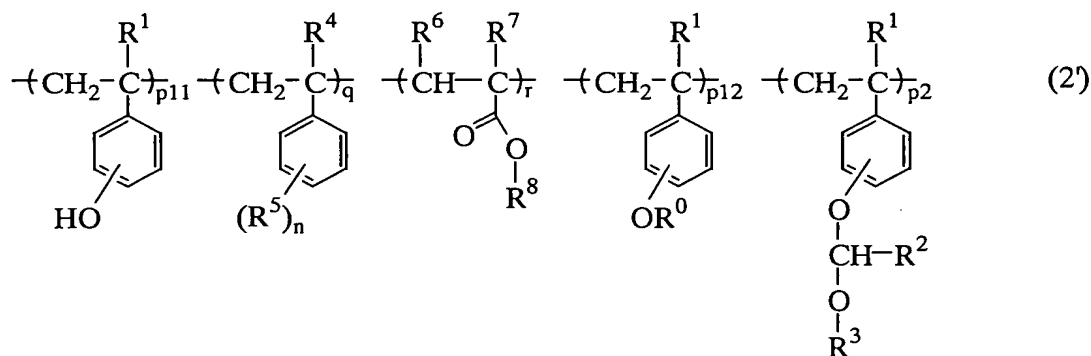
R<sup>6</sup> and R<sup>7</sup> each are hydrogen, a methyl group, alkoxycarbonyl group having 2 to 10 carbon atoms, cyano group or halogen atom,

$R^8$  is a tertiary alkyl group of 4 to 20 carbon atoms,  
 $n$  is 0 or a positive integer of 1 to 4,  
 $p$  is a positive number,  $q$  and  $r$  each are 0 or a  
 positive number,  $q$  and  $r$  are not equal to 0 at the same  
 5 time,

$p_1$  is a positive number,  $p_2$  is 0 or a positive number,  
 and  $p_1 + p_2 = p$ .

2. The method of claim 1 wherein the polymer comprising  
 10 recurring units of formula (1) has been produced by an  
 anionic polymerization process.

3. A method for preparing a polymer comprising recurring  
 units of the following general formula (2'), said method  
 15 comprising the step of introducing acid labile groups into  
 phenolic hydroxyl groups on the polymer comprising recurring  
 units of formula (2) prepared by the method of claim 1,



20 wherein  $R^0$  is an acid labile group,  $p_{11}$  is 0 or a positive  
 number,  $p_{12}$  is a positive number,  $p_{11} + p_{12} = p_1$ ,  $R^1$  to  $R^8$ ,  $n$ ,  
 $p_1$ ,  $p_2$ ,  $q$  and  $r$  are as defined above.

4. A resist composition comprising the polymer comprising  
 25 recurring units of formula (2) obtained by the method of  
 claim 1.

5. A chemically amplified positive resist composition comprising

(A) an organic solvent,

(B) the polymer comprising recurring units of formula  
5 (2) or (2') obtained by the method of claim 1 as a base resin, and

(C) a photoacid generator.

10 6. A chemically amplified positive resist composition comprising

(A) an organic solvent,

(B) the polymer comprising recurring units of formula  
(2) or (2') obtained by the method of claim 1 as a base resin,

15 (C) a photoacid generator, and

(D) a dissolution inhibitor.

7. The resist composition of claim 5 further comprising  
(E) a basic compound.